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2-20-00  
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Chiang, Tony P.; Leeser, Karl F.; Brown, Jeffrey A.; Babcoke, Jason E.  
Assignee: Angstrom Systems, Inc.  
Title: Varying Conductance Out Of A Process Region To Control Gas Flux In  
An ALD Reactor  
Serial No.: Not yet known Filing Date: Herewith  
Examiner: Not yet known Group Art Unit: Not yet known  
Docket No.: M-11466 -8C US

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10/027592  
12/19/01

San Jose, California  
December 19, 2001

COMMISSIONER FOR PATENTS  
Washington, D.C. 20231

**INFORMATION DISCLOSURE STATEMENT  
UNDER 37 CFR § 1.97(b)**

Dear Sir:

Pursuant to 37 C.F.R. § 1.56, § 1.97 and § 1.98, Applicant wishes to call to the attention of the Examiner the documents cited in the enclosed form PTO 1449 and the following documents:

1. U.S. Serial No. 09/812,352 Filed March 19, 2001;
2. U.S. Serial No. 09/854,092 Filed May 10, 2001;
3. U.S. Serial No. 60/255,812 Filed December 15, 2000;
4. U.S. Serial No. 09/812,285 Filed March 19, 2001; and
5. U.S. Serial No. 09/812,486 Filed March 19, 2001.

Citation of these documents shall not be construed as:

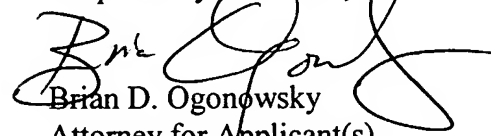
1. an admission that the documents are necessarily prior art with respect to the instant invention;
2. a representation that a search has been made, other than as described above or an admission that the information cited herein is, or is considered to be, material to

patentability as defined in § 1.56(b).

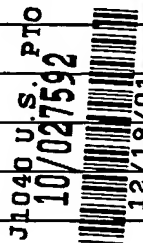
EXPRESS MAIL LABEL NO:

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Respectfully submitted,

  
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U.S. Department of Commerce, Patent and Trademark Office					Atty Docket No.		Serial No.	
					M-11466-8C US		Not yet known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT					Applicant(s)			
(Use several sheets if necessary)					Chiang, Tony P.; Leeser, Karl F.; Brown, Jeffrey A.; Babcoke, Jason E.			
					Filing Date		Group	
					Herewith		Not yet known	
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	5,855,675	01/05/99	Doering et al.	118	719		
	AB	5,879,459	03/09/99	Gadgil et al.	118	715		
	AC	5,916,365	06/29/99	Sherman	117	92		
	AD	6,174,377 B1	01/16/01	Doering et al.	118	729		
	AE	6,200,893 B1	03/13/01	Sneh	438	685		
	AF							
	AG							
	AH							
	AI							
	AJ							
	AK							
Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
	AL	1 052 309 A2	10/05/00	EP				
	AM	00/16377	03/23/00	PCT				
	AN							
	AO							
	AP							
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
	AQ	Peter Singer, Editor-in-chief, "Atomic Layer Deposition Targets Thin Films", Semiconductor International, September 1999, (pp. 40).						
	AR	"Ultra-thin films by atomic layer deposition", American Xtal Technology, October 1999 (pp. 37).						
	AS	S. M. Rosnagel, IBM Research, A. Sherman and F. Turner, Sherman and Associates, "Plasma-enhanced atomic layer deposition of Ta and Ti for interconnect diffusion barriers, J. Vac. Sci. Technol. B 18(4), Jul/Aug 2000, (pp. 2016-2020).						
Examiner			Date Considered					
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.</p>								